

ENGINEERING TRIPOS PART IIB

Wednesday 25 April 2012 2.30 to 4

Module 4C15

MEMS DESIGN

*Answer not more than **three** questions.*

All questions carry the same number of marks.

*The **approximate** percentage of marks allocated to each part of a question is indicated in the right margin.*

There are no attachments.

STATIONERY REQUIREMENTS

Single-sided script paper

SPECIAL REQUIREMENTS

Engineering Data Book

CUED approved calculator allowed

**You may not start to read the questions
printed on the subsequent pages of this
question paper until instructed that you
may do so by the Invigilator**

1 The schematic layout of a $10\ \mu\text{m}$ thick polysilicon surface-micromachined accelerometer is shown in Fig. 1. The proof mass has electrodes extending from either side to implement a differential capacitive sensing arrangement. The length of both fixed and movable electrodes is $750\ \mu\text{m}$ and the width of each electrode is $10\ \mu\text{m}$. The gap spacing between electrodes is $2\ \mu\text{m}$ and the electrode unit cell is replicated over a region that is $2.5\ \text{mm}$ in overall length with a spacing of $10\ \mu\text{m}$ between successive unit cells. The spring constant for the accelerometer is $10\ \text{Nm}^{-1}$ and the damping constant for the packaged device is $10^{-4}\ \text{Ns m}^{-1}$. The accelerometer operates at a temperature of $300\ \text{K}$.

- (a) If the effective mass along the sensitive axis is $10^{-7}\ \text{kg}$, estimate the resonant frequency for this device. Hence, or otherwise, calculate the static deflection of the proof mass for an input acceleration of $1g$ ($1g = 9.81\ \text{ms}^{-2}$) along the sensitive axis. [20%]
- (b) Estimate the total sense capacitance for the accelerometer. [20%]
- (c) Calculate the fractional change in capacitance for an input acceleration of $1g$ along the sensitive axis. [20%]
- (d) Calculate the rms thermo-mechanical noise-equivalent acceleration. [20%]
- (e) Comment on the process and design parameters that may be tuned to obtain a lower noise-equivalent resolution for this device. [20%]

Note that: permittivity of free space $\epsilon_0 = 8.854 \times 10^{-12}\ \text{F m}^{-1}$

Boltzmann constant $k_B = 1.381 \times 10^{-23}\ \text{J K}^{-1}$

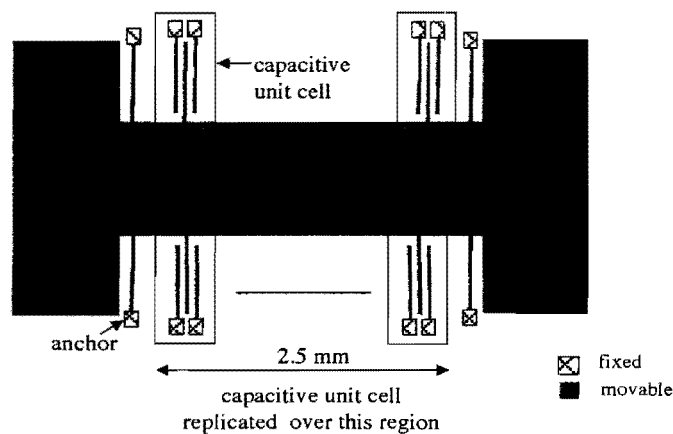


Fig. 1

2 A spring-supported proof mass is driven by a combination of a comb-drive actuator and a parallel plate actuator as shown in Fig. 2. At rest, each actuator has nominal overlap area A and nominal electrode gap spacing g_0 . You may assume that the structural thickness for the entire device is t and spring constant for the system is k . The damping in the system is negligible and the dielectric constant for air can be taken to be 1.

- (a) Derive an expression for the actuation force when the comb-drive and parallel-plate actuators are both driven by a common voltage V relative to the proof mass. [20%]
- (b) Derive an expression for the electrical spring constant for voltage-controlled actuator operation. [20%]
- (c) Derive an expression for the pull-in voltage and the corresponding value of the actuator displacement for voltage-controlled actuator operation. [50%]
- (d) Describe the relative advantages/disadvantages for this system of actuation as compared to the case of employing either the comb drive actuator or the parallel-plate actuator independently. [10%]

Hint: The real solution to a cubic equation of the form $x^3 + px = q$ is given by:

$$x = \left(\frac{q}{2} + \sqrt{\frac{p^3}{27} + \frac{q^2}{4}} \right)^{1/3} + \left(\frac{q}{2} - \sqrt{\frac{p^3}{27} + \frac{q^2}{4}} \right)^{1/3}$$

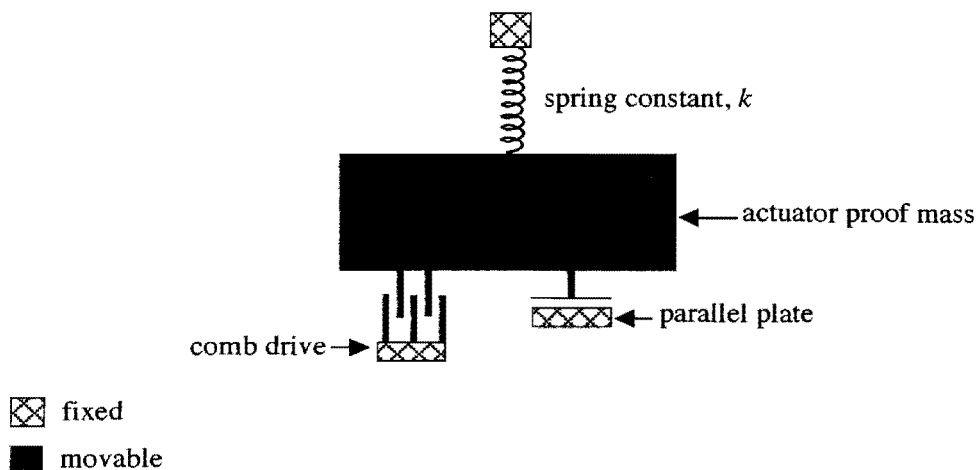


Fig. 2

3 (a) Explain briefly what is meant by the 6-12 Lennard-Jones relation expressing the interaction energy of two atoms. [15%]

(b) If two parallel plane surfaces of the same material are brought into close proximity then, considering only the *non-retarded* Lennard-Jones terms, the interaction energy per unit area $U(z)$, can be written as

$$U(z) = -\frac{A}{12\pi z^2}$$

where A is the Hamaker constant and z is the normal separation of the planes. If the two surfaces come into intimate atomic contact then $z \rightarrow h_0$ where h_0 is the equilibrium atomic spacing. The work of adhesion w can then be defined as the work done per unit area in increasing the separation of two such surfaces from h_0 to ∞ . Confirm that w and A are related by the expression

$$w = \frac{A}{12\pi h_0^2} . \quad [20\%]$$

(c) Explain briefly what is meant by the *Derjaguin approximation* when one of the surfaces is curved and of a radius which can be considered large in relation to the separation of the surfaces. [15%]

(d) Figure 3 shows a rigid *cylindrical* surface of radius R held at a minimum distance d above a plane surface. By considering the forces of attraction operating at position x and approximating the profile of the cylinder to the expression $y = x^2 / 2R$ derive an expression for the force of adhesion P' per unit length acting between the two solids in terms of the quantities w , h_0 , R and d . [40%]

(e) Comment on the feasibility of actually carrying out an experiment to validate your estimate of adhesion force. [10%]

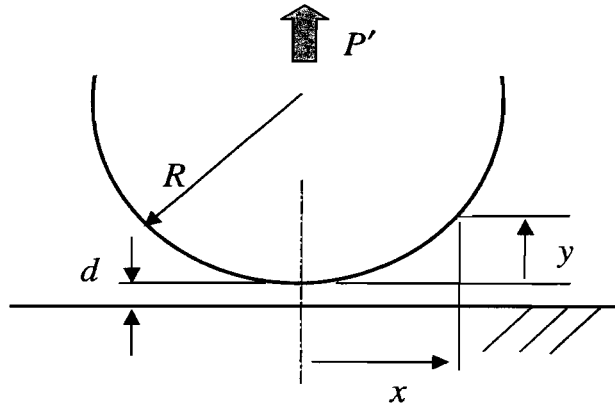


Fig. 3

4 A free-free beam polysilicon micro-resonator is shown in schematic layout in Fig. 4. It is driven into vibratory motion by a parallel-plate actuator of identical width and thickness. A separate parallel-plate electrode is symmetrically arranged on the opposite end of the micro-resonator to implement capacitive sensing of the motional current. The length L of the micro-resonator is $180\ \mu\text{m}$ and the width w of the device is $10\ \mu\text{m}$. The process-defined structural thickness h is $8\ \mu\text{m}$ and the nominal gap spacing g between the electrodes and the resonator is $1\ \mu\text{m}$. The Young's modulus E and density ρ of polysilicon may be assumed to be $160\ \text{GPa}$ and $2330\ \text{kg m}^{-3}$ respectively.

(a) The effective stiffness k and effective mass m for the fundamental mode of operation are given by

$$k = \frac{\pi^2}{8} \frac{Ewh}{L} \quad \text{and} \quad m = \frac{\rho whL}{2} .$$

Estimate the resonant frequency for the fundamental mode and sketch the mode shape. [20%]

(b) If the Quality Factor of the micro-resonator is 10^5 , calculate the amplitude of vibration at resonance for an applied micro-actuator DC voltage of $50\ \text{V}$ and an applied AC voltage of $1\ \text{V}$. For this case, estimate the amplitude of the motional current for a DC voltage of $50\ \text{V}$ applied between the sense electrode and the micro-resonator. [30%]

(c) Write down expressions for motional resistance, motional inductance and motional capacitance for the micro-resonator and calculate these values for a DC voltage of $100\ \text{V}$ applied between the micro-resonator and the electrodes. [30%]

(d) Sketch the dependence of the motional resistance on the applied DC voltage and the resonator gap. Comment on how the motional resistance may be minimised for this device. [20%]

Note that the permittivity of free space $\epsilon_0 = 8.854 \times 10^{-12}\ \text{F m}^{-1}$.

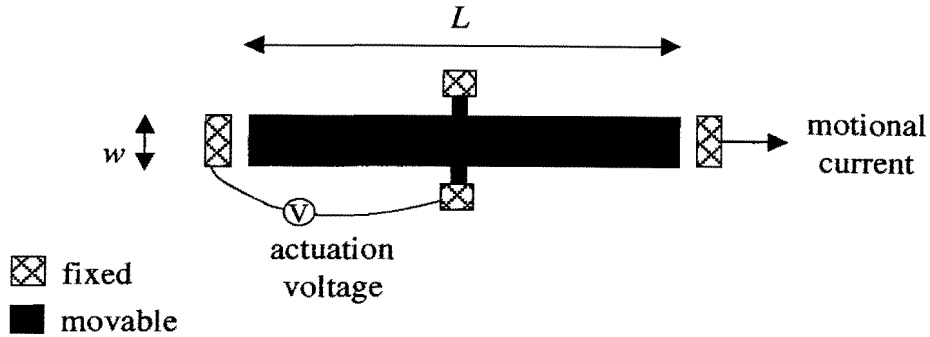


Fig. 4

Hertzian point contact under load P

Reduced radius R given by $\frac{1}{R} = \frac{1}{R_1} + \frac{1}{R_2}$

Contact modulus E^* by $\frac{1}{E^*} = \frac{1-\nu_1^2}{E_1} + \frac{1-\nu_2^2}{E_2}$

Radius of contact circle $a = \left\{ \frac{3PR}{4E^*} \right\}^{1/3}$

Maximum contact pressure $p_0 = \frac{3P}{2\pi a^2} = \left\{ \frac{6PE^{*2}}{\pi^3 R^2} \right\}^{1/3}$

Mean contact pressure $\bar{p} = \frac{2}{3} p_0$

Approach of distant points $\delta = \frac{a^2}{R} = \left\{ \frac{9P^2}{16RE^{*2}} \right\}^{1/3}$

Maximum shear stress is of magnitude $0.31p_0$ and at depth $0.48a$.

Smooth surface adhesion: $p(h) = \frac{8w}{3h_0} \left\{ \left(\frac{h}{h_0} \right)^{-3} - \left(\frac{h}{h_0} \right)^{-9} \right\}$

Elastic contact with adhesion, JKR: $\frac{4E^* a^3}{3R} = P + 2\sqrt{2\pi w E^* a^3}$